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Doros, Theodore G. Filing Date

December 5, 2003

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U.S. PATENT DOCUMENTS						
*Examiner Initials	Document Number	Issue Date	Name	Class	Subclass	Filing Date if Appropriate
and	5361292	11-1-94	Sweatt	378	34	
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Examiner Chris Lalwood	Date Considered Account 10,2004					
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